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FIG. 1

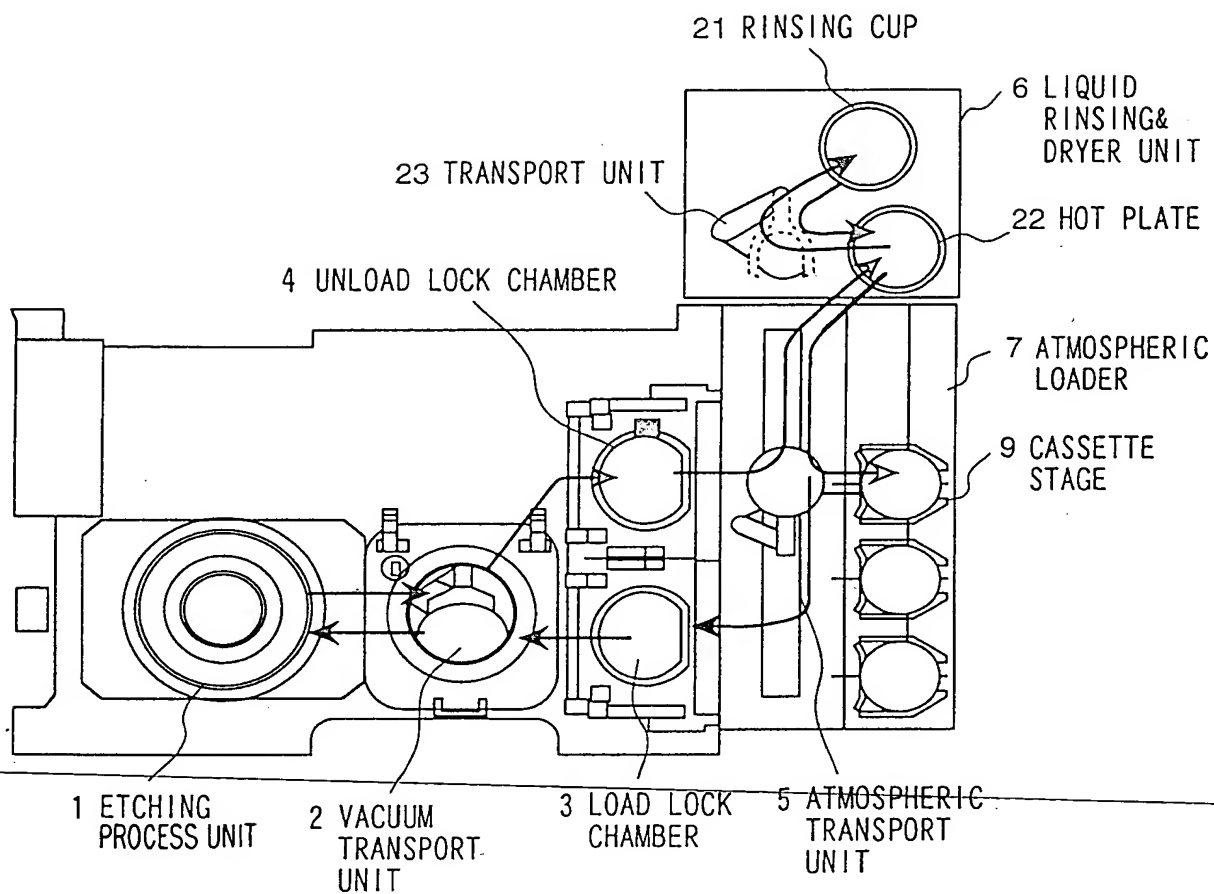


FIG.2

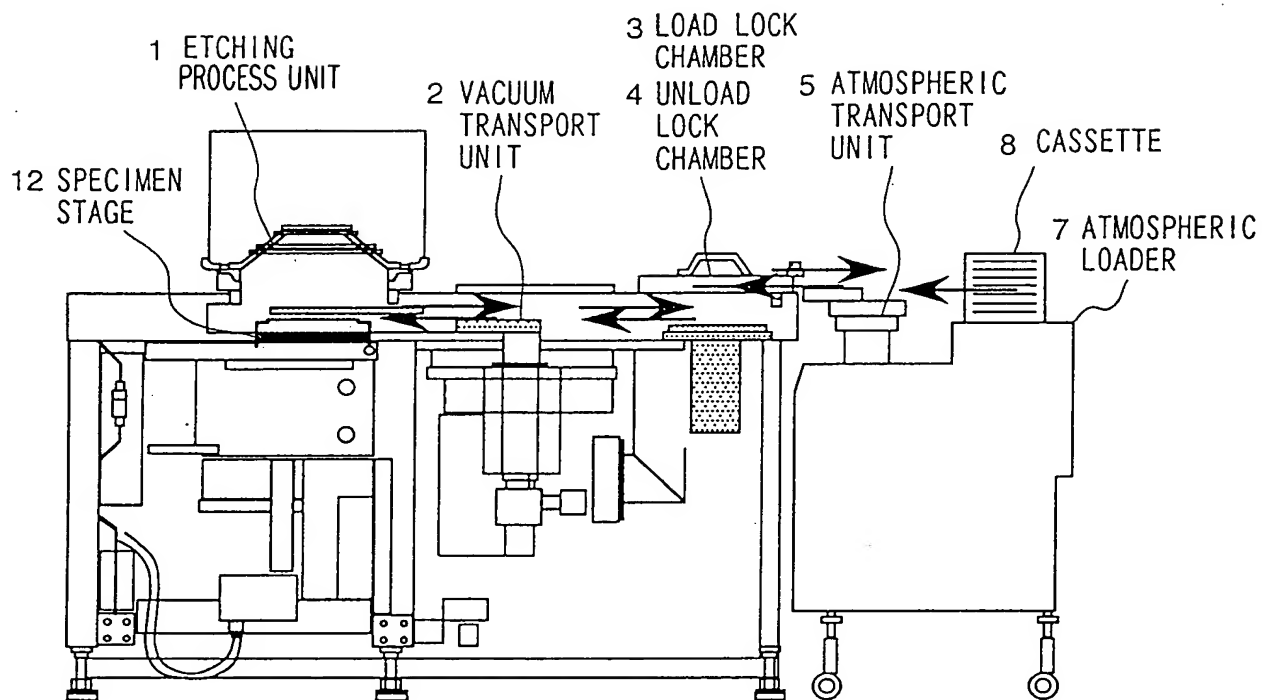
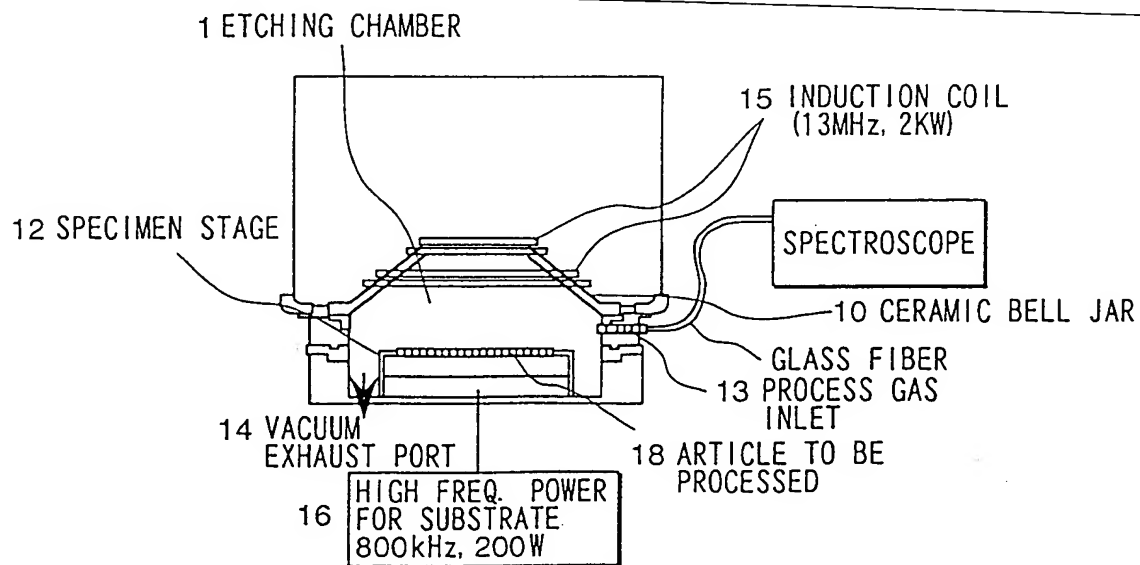


FIG.3





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FIG. 9

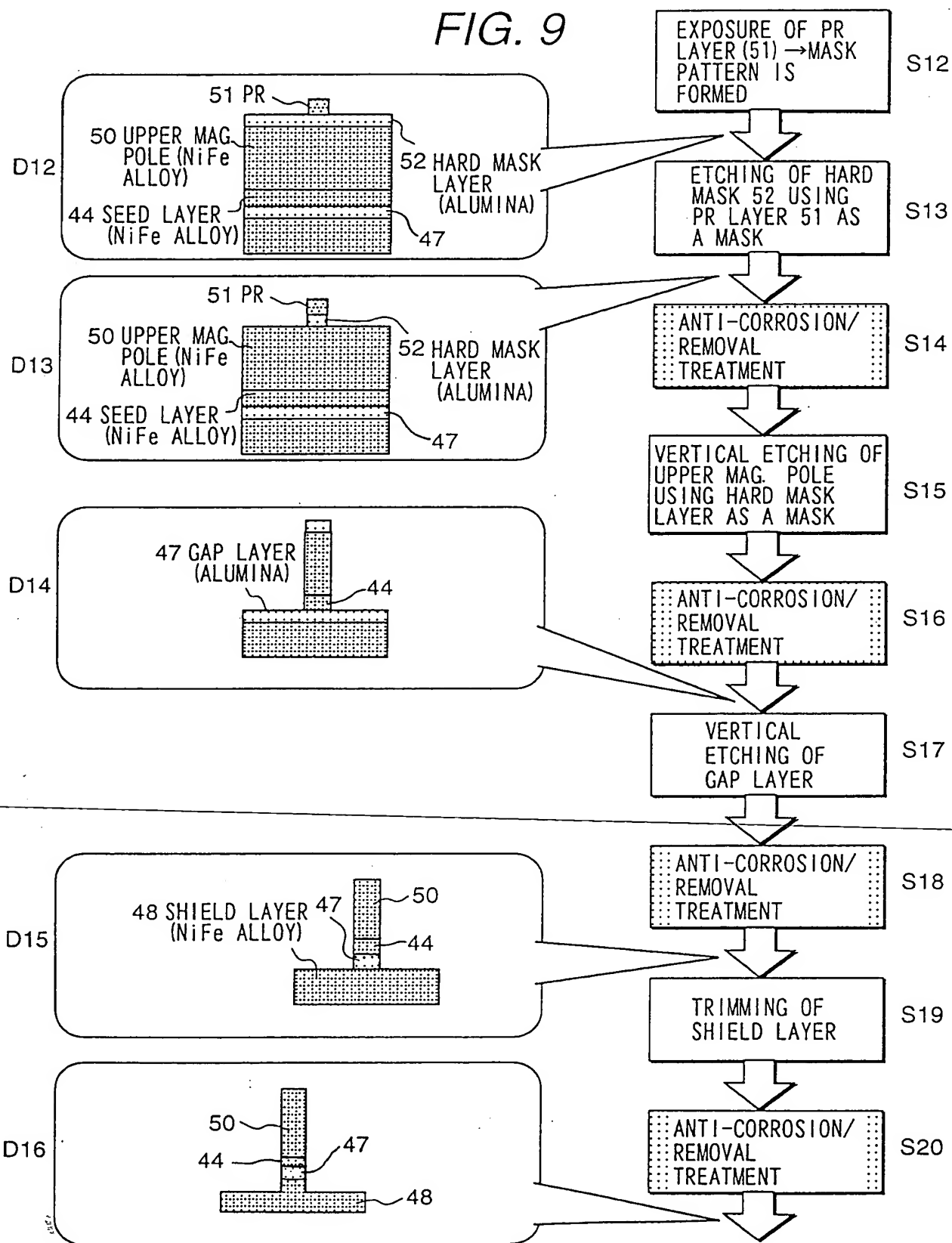


FIG.10

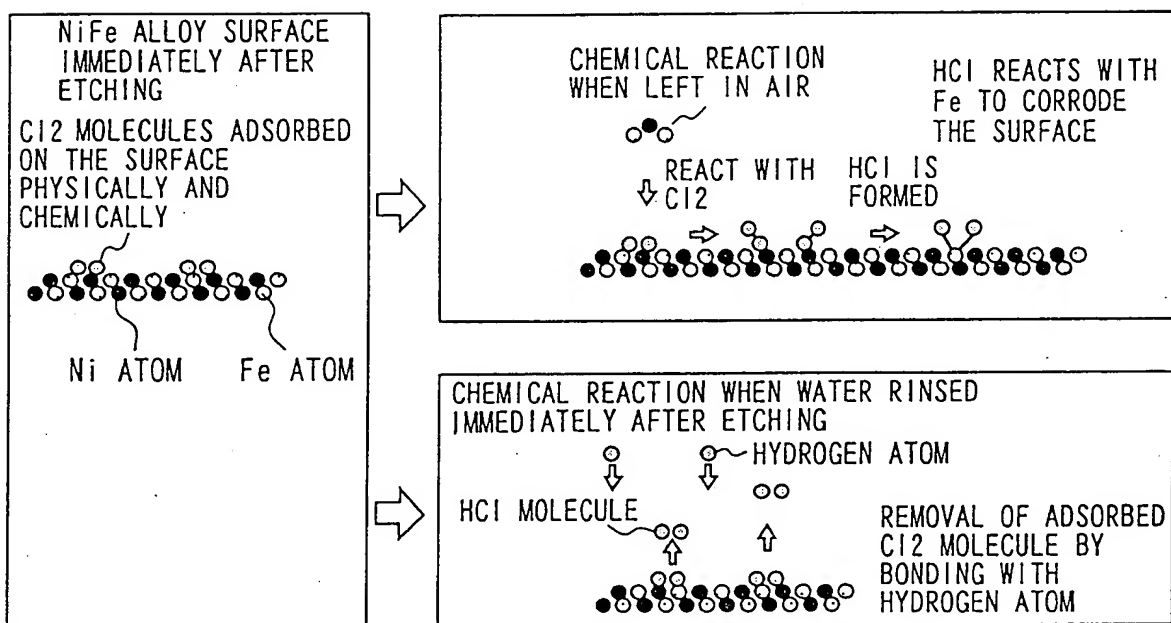


FIG.12

	BEFORE ETCHING	AFTER ETCHING
PLASMA ETCHING	<p>GAP LAYER</p>	
MILLING	<p>A LONGER INITIAL LENGTH OF UPPER MAGNETIC POLE NECESSITATED DUE TO LOW SELECTIVITY RATIO → DIFFICULT TO OBTAIN PRECISE SIZE CONTROL</p>	<p>DIFFICULT TO OBTAIN VERTICAL PATTERN</p>